CENTRAL INTELLIGENCE AGENCY REPORT

INFORMATION REPORT

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SUBJECT

Transistor Bauelemente erk fuer hnik "Carl NO. OF PAGES

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PLACE **ACQUIRED**

DATE OF

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von Ossietz

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SUPPLEMENT TO REPORT NO.

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"Carl von Ossietzky" (formerly the

Hans numication Engineering Plant under the supervision of inued at this enterprise rred to Dr boratory at the Dralowid Falter developed germanium basis with an indium. This development work was scheduled to be completed by the end of October 1954. Technical specifications for this type of transistor included:

Voltage Power output : up to 20 mW

: 50 to 100 V

Input

regel): 200 mV

Limit frequency: 1 to 3

Amplification: 50 to Sensitivity : 50 to oo ab total resistance in relation to

noise resistance measured at the equivalent input

resistance)

b. Development of two types of transistors for oscillators and amplifiers. It was also intended further to develop these transistors for frequencies from 5 to 10 Mc.

c. Development of germanium diodes in which pass voltage (Durchlass-Spannung) were at a current intensity of 10 mA. It is diodes, one for 2 and one for 5 mA. The

d. Experiments to manufacture resistances which have a boron-treated carbon layer. These resistances are believed to be much more efficient and much easie cture. Moreover, they are much more sensitive

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